

## RETRACTION

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# Retraction: Magnetic Fe<sub>3</sub>O<sub>4</sub>@NiO hierarchical structures: preparation and their excellent As(v) and Cr(vi) removal capabilities

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Retraction of 'Magnetic Fe<sub>3</sub>O<sub>4</sub>@NiO hierarchical structures: preparation and their excellent As(v) and Cr(vi) removal capabilities' by Shouwei Zhang *et al.*, *RSC Adv.*, 2013, **3**, 2754–2764, DOI: 10.1039/C2RA22495J.

The Royal Society of Chemistry, with the agreement of the named authors, hereby wholly retracts this *RSC Advances* article due to concerns with the reliability of the data in the published article. The authors requested to retract this article because they admitted that the TEM characterization of the Fe<sub>3</sub>O<sub>4</sub>@NiO hierarchical microspheres in Fig. 4c was duplicated from the characterization of Fe<sub>3</sub>O<sub>4</sub>@NiAl-LDH microspheres in Fig. S4B from a *J. Am. Chem. Soc.* paper by Mingfei Shao *et al.* without permission.<sup>1</sup> The authors would like to apologise to the authors of ref. 1, and for any inconvenience to readers.

Signed: Shouwei Zhang, Jiaying Li, Jinzhang Xu and Xiangke Wang

Date: 11th August 2021

Tao Wen was contacted but did not respond

Retraction endorsed by Laura Fisher, Executive Editor, *RSC Advances*

## References

- 1 M. Shao, F. Ning, J. Zhao, M. Wei, D. G. Evans and X. Duan, *J. Am. Chem. Soc.*, 2012, **134**(2), 1071–1077.

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